



PATENT

Atty. Dkt. No. AMAT/3032.C7/DSM/LOW K/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventive Application of:
Cheung, et al.

Serial No.: 10/647,959

Confirmation No.: 5142

Filed: August 26, 2003

For: Plasma Processes for
Depositing Low Dielectric
Constant Films

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

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Group Art Unit: 2818

Examiner: Thao P. Le

CERTIFICATE OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on <u>4/28</u> , 2004 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.	
<u>4/28/04</u> Date	<u>[Signature]</u> Signature

RESPONSE TO OFFICE ACTION DATED MARCH 26, 2004

In response to the Office Action dated March 26, 2004, having a shortened statutory period for response set to expire on June 26, 2004, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/3032.C7/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper. **Remarks** begin on page 5 of this paper.